

DISCUSSION OF THE CLAIMS

Claims 1-3, 6-10 and 13-26 are pending in the present application. Claims 4-5 and 11-12 are canceled claims. Claims 16-25 are presently withdrawn from active prosecution. Claim 26 is a new claim. Support for the new claims is found in the examples. Independent Claim 1 is amended herein to recite an inorganic-organic silicon network such as that described in the paragraphs [0022]-[0023] of the PG publication corresponding with the present application, i.e., U.S. 2008/0020190. The amine and hydroxyl groups of the inorganic-organic network now-recited in Claim 1 finds explicit support in the specification in the compound of Formula I (paragraph [0022]) and the reaction products of paragraph [0023]. The claims are further amended for matters of form and to address the objections/rejections set forth on page 3 of the July 9, 2010 Office Action.

No new matter is believed to have been added by this amendment.

REMARKS/ARGUMENTS

Independent Claim 1 now requires the inclusion of an inorganic-organic silicon network that includes an organic component having both a hydroxyl (OH) and an amine (NH) group on an organic component that is covalently bonded between silicon atoms.

Applicants submit that the art of record, i.e., Penth (U.S. 6,309,545) and Armbrust (U.S. 6,828,381), fail to disclose or suggest the particular inorganic-organic structure now recited in Claim 1.

Applicants respectfully request withdrawal of the rejection.

Irrespective of the amendment to Claim 1, Applicants submit the rejection of the previously presented claims over the combination of Penth and Armbrust is not supportable. The Penth and Armbrust compositions are substantially different. While Penth describes inorganic compositions, Armbrust describes compositions that include a copolymer such as an acrylate copolymer (see the Abstract of the Armbrust patent). The polymer-containing compositions of Armbrust are substantially different from the inorganic compositions of Penth. Applicants submit that those of skill in the art would have no basis for modifying the inorganic compositions of Penth in the manner of Armbrust at least for the reason that the Penth compositions are free from the organic components described in the Armbrust patent.

Further still the Armbrust compositions are excluded from the present claims which recite a ceramic coating layer than consists of a silicon network linked together by Si-O-Si bridges.

Applicants thank Examiner Matzek for the helpful and courteous discussion of August 11, 2010. During the discussion Applicants' U.S. representative pointed out that the cited art fails to disclose ceramic compositions containing the inorganic-organic silicon network described in the present claims.

With respect to the inclusion of the term POSS in Claim 8, Applicants point out that this term is explicitly defined in the specification and thus those of skill in the art would readily appreciate the metes and bounds of the claimed invention.

Applicants respectfully request withdrawal of the rejection and the allowance of all now-pending claims.

REQUEST FOR REJOINDER

Claims 16-25 are presently withdrawn from active prosecution. Each of the withdrawn claims depends directly or indirectly from Claim 1. Upon finding that the subject matter of Claim 1 is patentable, the Office is requested to kindly rejoin and allow the presently withdrawn claims.

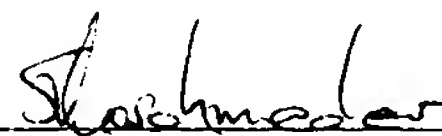
INFORMATION DISCLOSURE STATEMENT

Applicants submitted an IDS on July 8, 2010 including two PTO 1449 forms citing various U.S. patents and patent applications. Applicants' July 8, 2010 submission is before the mailing date of the Office's July 9, 2010 Office Action.

In the next communication the Office is requested to provide a signed and dated copy of the PTO 1449s of July 8, 2010 to acknowledge consideration of the references cited thereon during the prosecution of the present application.

Respectfully submitted,

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